

# NANO 36™

## Thin Film Deposition System



**Kurt J. Lesker®**  
Company

**PROCESS EQUIPMENT™**  
DIVISION

### Applications

- An affordable deposition system designed for entry to mid-level users in university, industrial, and government laboratories
- R&D thin film deposition
- Electron microscope sample preparation

### Features

- 12" diameter X 18" high glass Pyrex® bell jar with implosion guard
- Manual touch-screen PC based process automation
- 700 l/s diffusion or optional turbomolecular high vacuum pumping
- Compact form factor

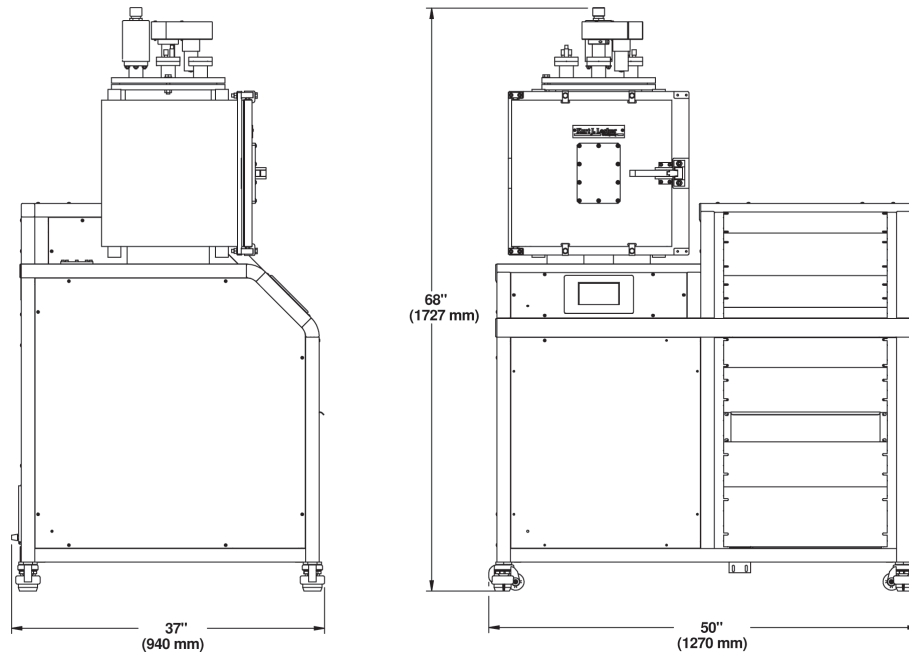
### Process Modules

- Magnetron sputtering: RF, DC, Pulsed DC
- Thermal evaporation, up to four sources, with film thickness monitor or control package

### Options

- 12" diameter X 18" high stainless steel bell jar or 18" box stainless steel chamber with aluminum door and viewport
- Primary substrate rotation and/or tilt
- Back side quartz lamp heating to 350°C
- Water cooled platen assembly
- 2-channel upstream pressure control (with sputtering module)
- On-site installation and training

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Dimensions Approximate: Shown with stainless steel box chamber.

## Specifications

Process Chamber Volume	Glass Bell Jar - 27 liters Stainless Steel Bell Jar - 28 liters Stainless Steel Box Chamber - 45 liters
Process Chamber Geometry	Glass Bell Jar - 12" (305mm) diameter X 18" (457mm) high Stainless Steel Bell Jar - 12" (305mm) diameter X 18" (457mm) high Stainless Steel Box Chamber - 16" (406mm) W X 16" (406mm) D X 16" (406mm) H
Process Chamber Construction	Glass Bell Jar - Pyrex® Glass Stainless Steel Bell Jar - 304L Stainless Steel Stainless Steel Box Chamber - 304L Stainless Steel with 6061 Aluminum Hinged Door
Cabinet Construction	Carbon Steel, Gray Powder Coat Finish with Swivel Casters
Deposition Sources	Torus® Magnetron Sputtering Cathode Multiple Boat Source Thermal Evaporation
Deposition Orientation	Sputter Up; Evaporation Up
Substrate Size (max)	Single, up to 8" (200mm) with optional 20 RPM max variable rotation
Substrate Heating	Quartz Lamps, to 350°C
Standard Vacuum Pumping	700 l/sec Diffusion Pump, Optional 260 and 685 l/sec Turbo Pumps Available
Gauging	Wide Range Vacuum Gauge
Base Pressure	Turbo Pump (CDE) $5 \times 10^{-7}$ Torr ( $6.7 \times 10^{-7}$ mbar)
Process Gas	Optional 2 Channel Mass Flow Control with Pressure Control
System Control	PC-Based HMI with Color Touch Screen
Required Power (typical, based on options)	208VAC, 1Ø, 50/60 Hz; Optional 380VAC, 3Ø, 50/60 Hz
Available Certifications, Markings	CE and CSA
Warranty	12 Months Upon Shipment
Rack Dimensions (approx)	50" X 37" X 68"high (1270mm X 940mm 1727mm)
Weight (approx)	1,200 lbs (544 kg)

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